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The ionic equilibrium in the CuSO₄–H₂SO₄–H₂O system and the formation of the honeycomb-like structure during copper electrodeposition

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Abstract: The ionic equilibrium of the species in the CuSO₄–H₂SO₄–H₂O system was employed to systematize the conditions of copper electrodeposition leading to the formation of the honeycomb-like structure. The reason why CuSO₄ concentrations higher than 0.15 M are unsuitable for the formation of honeycomb-like structures is shown. The range of H₂SO₄ concentrations enabling the formation of this type of structure was also determined. The conditions leading to the formation of the honeycomb-like structures are: electrodeposition from solutions with lower concentrations of Cu(II) ions (0.15 M CuSO₄ and less) in a concentration range from 0.25 to 1.0 M H₂SO₄, at a temperature of 18.0±1.0 °C and at overpotentials outside the plateau of the limiting diffusion current density at which hydrogen evolution is vigorous enough to change the hydrodynamic conditions in the near-electrode layer.

Keywords: electrolysis; hydrodynamics; morphology; hydrogen; copper.

INTRODUCTION

Aqueous solutions of sulfuric acid and cupric sulfate are frequently found in copper hydrometallurgical processes, such as leaching, solvent extraction, electrowinning and electrorefining.¹ Irregular deposits, such as powder deposits^{2–5} and open and porous structures with an extremely high surface area,⁶ denoted as honeycomb-like ones,^{7–9} are most often formed by electrodeposition from these solutions. The main species present in aqueous sulfuric acid solutions containing Cu(II) are: bisulfate ions (HSO_4^-), cupric ions (Cu^{2+}), aqueous cupric sulfate ($\text{CuSO}_4\text{(aq)}$), hydrogen ions (H^+) and sulfate ions (SO_4^{2-}).¹ In an aqueous so-

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lution of sulfuric acid and cupric sulfate, two weak electrolytes, HSO_4^- and $\text{CuSO}_4\text{(aq)}$ are formed and the equilibriums between HSO_4^- , H^+ and SO_4^{2-} ions, as well as between $\text{CuSO}_4\text{(aq)}$, Cu^{2+} and SO_4^{2-} species are constituted.¹

Electrochemical processes dealing with the formation of irregular deposits are very suitable for the analysis of the ionic equilibrium in the $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ system, due to the hydrogen evolution reaction which occurs parallel to copper electrodeposition. The first report which investigated the effect of this ionic equilibrium on the formation of these deposits was reported recently.¹⁰ Considering the high technological significance of honeycomb-like structures as possible electrodes in many electrochemical devices, such as fuel cells, batteries and sensors,⁶ a detailed analysis of the ionic equilibrium in the $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ system on the formation of this type of deposit was until this study necessary.

EXPERIMENTAL

Copper was potentiostatically deposited from the following solutions: 0.075 M CuSO_4 + 0.50 M H_2SO_4 , 0.30 M CuSO_4 + 0.50 M H_2SO_4 , 0.60 M CuSO_4 + 0.50 M H_2SO_4 and 0.15 M CuSO_4 + 0.125 M H_2SO_4 .

The electrodepositions were performed in an open cell at a temperature of 18.0 ± 1.0 °C using a Wenking 7103 Girh potentiostat. Doubly distilled water and analytical grade chemicals were used for the preparation of the solutions for the electrodeposition of copper.

The electrodepositions of copper were performed at an overpotential of 1000 mV onto cylindrical copper cathodes previously covered by a thin copper film.

The counter electrode was a copper foil placed close to the walls of the cell; the working electrode was placed in the middle of the cell, while the overpotential was adjusted *vs.* a copper electrode which was positioned at a distance of 0.2 cm from the surface of the working electrode.

For the determination of the average current efficiency of hydrogen evolution, an electrochemical cell with the same arrangement of copper electrodes as that used for the preparation of the copper deposits for SEM analysis was employed. The electrodes were situated under a burette with the surface facing up so that the total amount of hydrogen evolved during the electrodeposition processes went into the burette. During the electrodeposition process, the volume of evolved hydrogen, $V(\text{H}_2)$, and the current of the electrodeposition, I , after a time, t , were recorded. Then, after graphical integration $I-t$, the average current efficiency for hydrogen evolution in a time t , $\eta_{I,\text{av}}(\text{H}_2)$, was determined according to Eq. (1):

$$\eta_{I,\text{av}}(\text{H}_2) = \frac{nFV(\text{H}_2)}{V \int_0^t Idt} \quad (1)$$

where nF is the number of Faradays per mole of consumed ions and V is the molar volume of a gas under normal conditions (*i.e.*, 22.400 dm³).

The average current efficiency for hydrogen evolution, $\eta_{\text{av}}(\text{H}_2)$, is defined as the average value of the $\eta_{I,\text{av}}(\text{H}_2)$ values over the total electrolysis time.

A detailed procedure for the determination of the average current efficiency of hydrogen evolution has already been given.⁷

SEM Microphotographs corresponding to morphologies of copper deposits, obtained with a quantity of electricity of $10.0 \text{ mA h cm}^{-2}$, were recorded on scanning electron microscope (SEM) JOEL, model T20, and a Tescan Digital Microscope.

RESULTS AND DISCUSSION

The copper deposits obtained at an overpotential of 1000 mV from 0.075, 0.30 and 0.60 M CuSO_4 in 0.50 M H_2SO_4 are shown in Fig. 1. For all these solutions, an overpotential of 1000 mV is for 250 mV higher than the plateaus of the limiting diffusion current density.¹¹ As can be seen from Fig. 1, holes formed due to attached hydrogen bubbles were the main morphological form obtained under these electrodeposition conditions. The shape of the obtained holes changed with increasing CuSO_4 concentration, from those forming a honeycomb-like structure to dish-like ones and the mechanism of their formation has been widely studied.^{7,8,11}

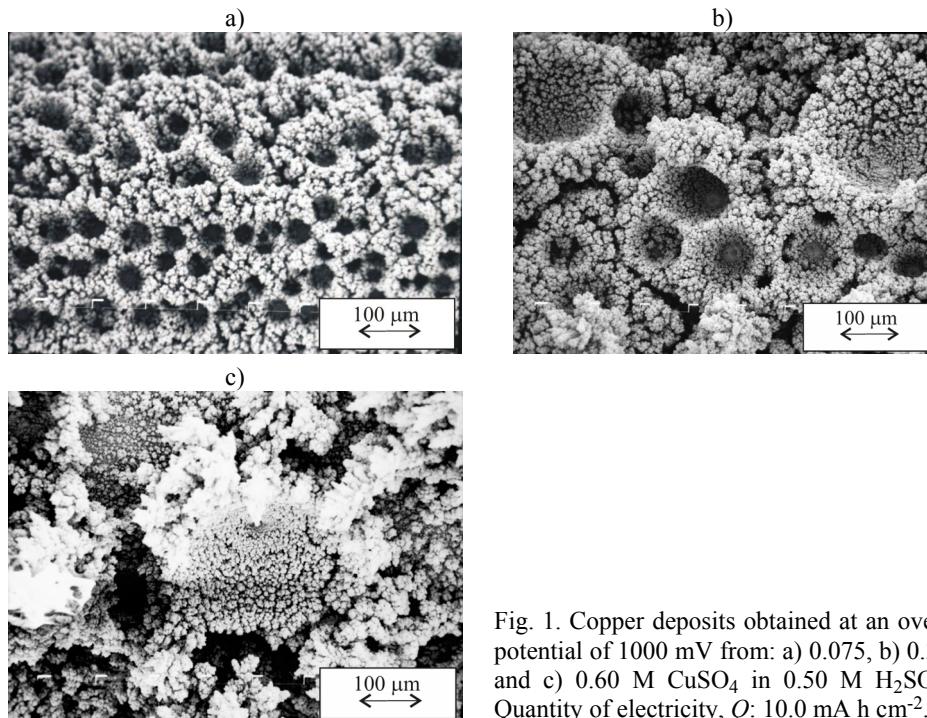


Fig. 1. Copper deposits obtained at an overpotential of 1000 mV from: a) 0.075, b) 0.30 and c) 0.60 M CuSO_4 in 0.50 M H_2SO_4 . Quantity of electricity, Q : $10.0 \text{ mA h cm}^{-2}$.

The average current efficiencies of hydrogen evolution, $\eta_{av}(\text{H}_2)$, obtained under these electrodeposition conditions were 68.7, 16.0 and 4.6 % from 0.075, 0.30 and 0.60 M CuSO_4 in 0.50 M H_2SO_4 , respectively.¹¹ These values were derived from the dependences of the current of electrodeposition and the volume of evolved hydrogen on the electrodeposition time, as shown in Fig. 2. It can be seen from Fig. 2 that increasing the concentration of CuSO_4 led to a decrease of

the quantity of evolved hydrogen and, hence, the average current efficiencies of hydrogen evolution. At the first sight, this was unexpected because the concentration of H_2SO_4 was the same in all the solutions. The explanation for it can be obtained by analysis of the ionic equilibrium of the species in the $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ system. The dependence of the relative concentration of hydrogen ions (H^+) on the H_2SO_4 concentration for different concentrations of copper ions is shown in Fig. 3. According to this equilibrium, increasing the copper ion concentration produces a sharp decrease in the hydrogen ion concentration, while increasing the concentration of sulfuric acid produces an increase in the hydrogen ion concentration.¹ The reason for this is that the addition of sulfuric acid to the solution decreases the concentration of free sulfate ions due to the formation of bisulfate ions, while the addition of cupric sulfate to the solution increases the concentration of bisulfate ions and decreases the concentration of hydrogen ions.

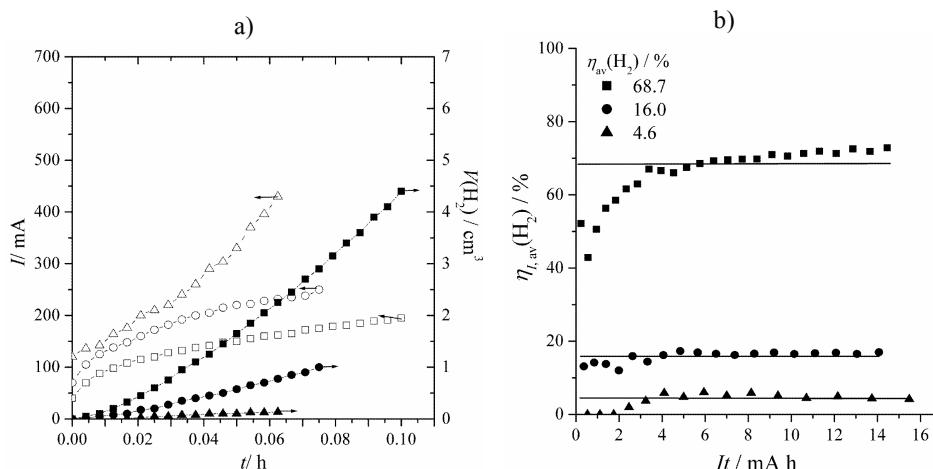


Fig. 2. The dependences of the current of copper electrodeposition and the volume of evolved hydrogen on the electrodeposition time (a) and the average current efficiencies for hydrogen evolution reaction on the quantity of used electricity (b) for copper electrodeposition at 1000 mV from 0.075 (□, ■), 0.30 (○, ●) and 0.60 M (△, ▲) CuSO_4 in 0.50 M H_2SO_4 .

It is very clear that the decrease of the quantity of evolved hydrogen, and consequently, the average current efficiencies of hydrogen evolution (Fig. 2) is the result of decreasing the hydrogen ion concentration with the increasing copper concentration. Moreover, the acceleration of the electrochemical processes with increasing CuSO_4 concentration had an unfavorable effect on the formation of the honeycomb-like structures. It was found¹² that the maximum CuSO_4 concentration (in 0.50 M H_2SO_4) which allowed the formation of the honeycomb-like structure was 0.15 M. Hydrogen evolution, which leads to the formation of the honeycomb-like structures, was vigorous enough to change the hydrodynamic conditions in the near-electrode layer. For copper sulfate solutions containing 0.15 M

CuSO_4 and less, in 0.50 M H_2SO_4 , the critical quantity of evolved hydrogen leading to a change in the hydrodynamic conditions was estimated to correspond to $\eta_{\text{av}}(\text{H}_2)$ of 10.0 %.¹² This was attained by electrodeposition at an overpotential of 800 mV from 0.15 M CuSO_4 in 0.50 M H_2SO_4 .⁷

Vigorous hydrogen evolution is only one of the possible ways of changing the hydrodynamic conditions in the near-electrode layer. For example, a change in the hydrodynamic conditions can also be realized under imposed magnetic field (magnetohydrodynamic effects),^{13–15} in an ultrasonic field¹⁶ or by rotating the electrode.¹⁷

The above analysis of the electrodeposition processes with the different CuSO_4 concentrations and the same H_2SO_4 concentration corresponds to a vertical analysis of the ionic equilibrium of the species in the $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ system. Horizontal analysis of this ionic equilibrium can be performed by analysis of the electrodeposition processes with a constant CuSO_4 concentration and different H_2SO_4 concentrations.

For the horizontal analysis, 0.15 M CuSO_4 was selected, while the selected H_2SO_4 concentrations were higher (1.0 M) and lower (0.125 and 0.25 M) than 0.50 M. According to the ionic equilibrium shown in Fig. 3, the H^+ concentration is higher for these solutions (the position of the Cu^{2+} concentration of 0.15 M can easily be calculated) than for copper solutions containing 0.30 and 0.60 M CuSO_4 in 0.50 M H_2SO_4 . This was confirmed by the higher average current efficiencies of hydrogen evolution obtained at an overpotential of 1000 mV from these solutions than those obtained from 0.30 and 0.60 M CuSO_4 in 0.50 M H_2SO_4 . The average current efficiencies of hydrogen evolution, $\eta_{\text{av}}(\text{H}_2)$ were: 20.3 % from 0.15 M CuSO_4 in 0.125 M H_2SO_4 , 26.4 % from 0.15 M CuSO_4 in 0.25 M H_2SO_4 and 45.7 % from 0.15 M CuSO_4 in 1.0 M H_2SO_4 .¹⁸ Based on the obtained values, it was expected that honeycomb-like structures would be obtained by electrodeposition from these solutions. However, honeycomb-like structures were only formed from 0.15 M CuSO_4 in both 1.0 M and 0.25 M H_2SO_4 but not from 0.15 M CuSO_4 in 0.125 M H_2SO_4 .¹⁸ The copper deposit obtained at an overpotential of 1000 mV from 0.15 M CuSO_4 in 0.125 M H_2SO_4 is shown in Fig. 4. Analysis of this copper deposit identified the presence of holes with shoulders of degenerated dendrites, and irregular channels formed by evolved hydrogen around the dendritic and cauliflower-like particles. The appearing of these morphological forms clearly indicates that the hydrodynamic conditions in the near-electrode layer remained unchanged during electrodeposition from this solution. This was very surprising owing to the very high average current efficiency of hydrogen evolution under which this deposit was formed. This indicates that the quantity of evolved hydrogen is not the only parameter responsible for a change in the hydrodynamic conditions in the near-electrode layer. Therefore, the recognition of the properties of the electrodeposition solutions, such as density

and surface tension, is very important.¹⁸ The addition of H₂SO₄ to an electroplating solution increases the density^{18,19} and decreases the surface tension of an electroplating solution.¹⁸ An increase of the density and a lowering of the surface tension of the solution decreases the break-off diameter of a hydrogen bubble^{18,20} and, consequently, reduces the time required to achieve the critical size for its detachment from the electrode surface. Electrodeposition processes from such solutions will produce an sufficient amount of hydrogen bubbles which can cause an effective stirring of solution in the near-electrode layer and change the hydrodynamic conditions. This can be confirmed by the analysis of number of holes formed per mm² of surface area of the copper electrodes and the average diameter of holes obtained from 0.15 M CuSO₄ in 0.50 M H₂SO₄ at 800 mV (the formed honeycomb-like structure with a $\eta_{av}(H_2)$ of 10.8 %; changed hydrodynamic conditions in the near-electrode layer) and from 0.15 M CuSO₄ in 0.125 M H₂SO₄ at 1000 mV (the honeycomb-like structure was not formed with a $\eta_{av}(H_2)$ of 20.3 %; insufficient change of the hydrodynamic conditions in the near-electrode layer). The number of holes formed due to the attached hydrogen bubbles from 0.15 M CuSO₄ in 0.50 M H₂SO₄ at 800 mV was 10 per mm² of surface area of the copper electrode,⁷ while their average diameter was 98.7 μm. This number was for about 40 % larger than the number of holes formed from 0.15 M CuSO₄ in 0.125 M H₂SO₄ at 1000 mV. The average diameter of the holes formed from 0.15 M CuSO₄ in 0.125 M H₂SO₄ at 1000 mV was about 20 % larger than the average diameter of those formed from 0.15 M CuSO₄ in 0.50 M H₂SO₄ at 800 mV.

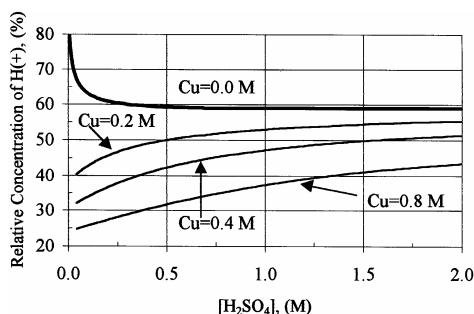


Fig. 3. Relative concentration of hydrogen ions as function of sulfuric acid and total copper concentrations, at 25 °C ($c_{RH^+} = [H^+]/[HT]$) (Reprinted with permission of Elsevier).¹

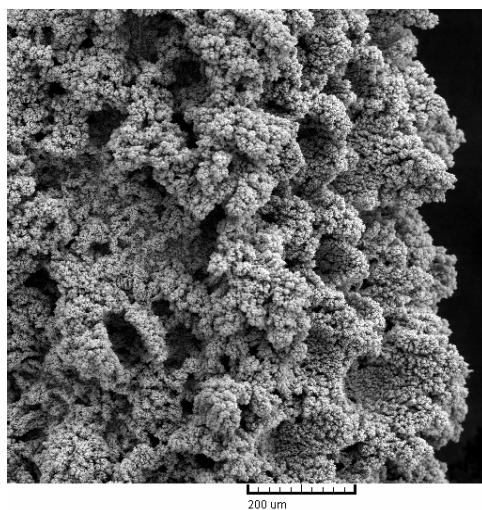


Fig. 4. The copper deposit obtained at an overpotential of 1000 mV from 0.15 M CuSO₄ in 0.125 M H₂SO₄. Quantity of electricity: 10.0 mA h cm⁻².

The acceleration of electrochemical processes through increasing the temperature of electrolysis had an unfavorable effect on the formation of honeycomb-like structures.²¹ Increasing the temperature led to a decrease in the number of holes because of the effect of temperature on some properties of the solutions, such as viscosity and surface tension.^{20–22}

Horizontal and vertical analysis of the ionic equilibrium in the $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ system enabled the electrodeposition conditions leading to the formation of honeycomb-like structures to be systematized. It explained why CuSO_4 concentrations higher than 0.15 M are unsuitable for the formation of this type of structures. The minimal H_2SO_4 concentration of 0.25 M H_2SO_4 (for 0.15 M CuSO_4) allowing the formation of honeycomb-like structures was also determined.

CONCLUSIONS

Systematization of the electrodeposition conditions allowing the formation of honeycomb-like copper structures from acid sulfate solutions was made by analyzing the ionic equilibrium in the $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ system. The honeycomb-like structures can be formed by electrodeposition from solutions with low concentrations of $\text{Cu}(\text{II})$ ions (0.15 M CuSO_4 and less) in an H_2SO_4 concentration in the range from 0.25 to 1.0 M, at a temperature of 18.0 ± 1.0 °C, and at overpotentials positive with respect to the plateau of the limiting diffusion current density at which hydrogen evolution is vigorous enough to change the hydrodynamic conditions in the near-electrode layer.

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И З В О Д

ЈОНСКА РАВНОТЕЖА У СИСТЕМУ $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ И ФОРМИРАЊЕ СТРУКТУРЕ ПЧЕЛИЊЕГ САЋА ЕЛЕКТРОХЕМИЈСКИМ ТАЛОЖЕЊЕМ БАКРА

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Анализирана је јонска равнотежа у систему $\text{CuSO}_4\text{--H}_2\text{SO}_4\text{--H}_2\text{O}$ да би се систематизовали услови електрохемијског таложења бакра који доводе до формирања структуре пчелињег саћа. Показано је да су концентрације CuSO_4 веће од 0,15 M непогодне за формирање структуре пчелињег саћа. Одређен је и опсег концентрација H_2SO_4 у којем се формира оваква структура. Услови који доводе до формирања структуре пчелињег саћа су: електрохемијско таложење из раствора са концентрацијом $\text{Cu}(\text{II})$ од највише 0,15 M и опсегом концентрација H_2SO_4 од 0,25 до 1,0 M, температуре од 18.0 ± 1.0 °C, и на пренапетостима позитивнијим од оних који одговарају платоу граничне дифузионе густине струје, на којима

је издвајање водоника довољно интензивно да промени хидродинамичке услове у прикаподном слоју.

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